

the **abdus salam** international centre for theoretical physics

ICTP 40th Anniversary

SCHOOL ON SYNCHROTRON RADIATION AND APPLICATIONS In memory of J.C. Fuggle & L. Fonda

19 April - 21 May 2004

Miramare - Trieste, Italy

1561/12

Microscopy Optics

W. Jark



Optics for x-ray microscopy

µXFA beamline and multilayer laboratory

Werner Jark

Sincrotrone Trieste Basovizza (TS), Italy



werner.jark@elettra.trieste.it

http://www.elettra.trieste.it/experiments/beamlines/microfluo/index.html

Werner Jark ELETTRA



Structure of lecture

 $\ensuremath{\mu XFA}$ beamline and multilayer laboratory

Discussion of the technical aspects of x-ray microscopy (learn about applications in three weeks)

- Spatial resolution obtainable with different objectives based
 - on reflection
 - on diffraction
 - on refraction

W.C. Roentgen: There are no refractive lenses for x-rays!

• Refractive objectives unique to x-rays

Note: This presentation is neither historically correct as a whole nor complete for the single items. It is limited to (often newer) experiments, which can explain the concepts in the most instructive way.

Werner Jark ELETTRA



Why microscopy with SR?

µXFA beamline and multilayer laboratory

A) use unconventional contrast mechanisms, e.g.

- absorption edges (water window)
- dichroic response (helicity)
- coincidences more in 3 weeks

B) in visible: spatial resolution \approx light wavelength

will shorter wavelength SR reveal the yet unseen?

Werner Jark ELETTRA



Why x-ray microscopy?

µXFA beamline and multilayer laboratory



ELETTRA

In memory of J.C. Fuggle and L. Fonda, Trieste, 28/04/2004



Why x-ray microscopy?

µXFA beamline and multilayer laboratory

Question: What is the ultimately possible spatial resolution?

Please note:

here we would like to see features in a single aggregate

X-ray crystallography instead reveals structures with very high spatial resolution, however, only of crystalline samples. "Lensless" or coherent x-ray diffraction imaging of intrinsically noncristalline objects promises high resolution (see elsewhere).

Werner Jark ELETTRA



Microscope objectives for visible

µXFA beamline and multilayer laboratory







FIG. 1. SO geometry and image formation.



Werner Jark ELETTRA





µXFA beamline and multilayer laboratory





Have to focus x-rays with refraction, reflection or diffraction with largest possible NA

Werner Jark ELETTRA



Characteristics of x-rays

 $\boldsymbol{\mu} \boldsymbol{X} \boldsymbol{F} \boldsymbol{A}$ beamline and multilayer laboratory

- wavelength of order of λ =0.06 nm (E=20 keV)
- negligible absorption in air
- large variation of absorption in material
- reflected with surface mirrors only at grazing incidence Φ (rule of thumb for Pt coating: E*Φ/[keV*mrad] = 80)
- reflected/monochromatised at lattice planes of highly regular crystal structures

Soft x-rays with 0.6 nm $< \lambda < 30$ nm (40 eV < E < 2 keV)

significant absorption in air (vacuum required) and material
mirrors for reflection, gratings for monochromatisation

Werner Jark ELETTRA



Some basic properties

µXFA beamline and multilayer laboratory



e.g. for plexiglass at λ =0.154 nm (8.05 keV): δ = 4.2 10⁻⁶ 1/ μ ≈ 1.3 mm then Φ = 2.9 mrad (0.167°) $\Delta(\gamma = 45°) = -8.4 \mu$ rad 1=36.67 μ m provide 2 π phase shift

Werner Jark ELETTRA



X-ray microscope schemes

µXFA beamline and multilayer laboratory



ELETTRA



X-ray microscope schemes

µXFA beamline and multilayer laboratory



Scanning Microscope

Ni 3p and Ga 3d images $(25x50 \ \mu m2)$ taken at (a) 25° C and (b) after annealing to 300° C, the R-Ga image in (b) manifests lateral variations in the interfacial reaction (c) C 1s image and entire spectrum measured in the C-rich spots (bottom) and in the non-defect region (top)



Werner Jark ELETTRA





ultimate limit practical limit experimental limit

µXFA beamline and multilayer laboratory





Werner Jark ELETTRA





ultimate limit practical limit experimental limit

µXFA beamline and multilayer laboratory

Reflection

Beam compression in multibounce capillary



Fig. 1. Profile of the inner diameter (ID) of a capillary measured with an optical microscope. The entering ID is 22 μ m and the exit ID is 3 μ m. The calculated trajectories of two rays from a parallel x-ray beam are shown. Ray 1 undergoes 12 successive bounces with a net throughput of 57%, as calculated by a two-dimensional ray-tracing program that includes the x-ray reflectance for each bounce. Ray 2 undergoes 11 reflections with a net throughput of 61%. The average reflectivity per bounce exceeds 95%, and the total deflection angles are 2.3 and 2.2 mrad, respectively.

201

Donald H. Bilderback,

R_{exp} ≈ 50 nm but very low efficiency better efficiency is routinely (commercially available) provided with

 $R_{exp} \approx 5 \ \mu m$

School on Synchrotron Radiation and Applications In memory of J.C. Fuggle and L. Fonda, Trieste, 28/04/2004

Werner Jark ELETTRA





ultimate limit practical limit experimental limit

µXFA beamline and multilayer laboratory





ultimate limit practical limit experimental limit

µXFA beamline and multilayer laboratory



In memory of J.C. Fuggle and L. Fonda, Trieste, 28/04/2004



ultimate limit practical limit experimental limit

 $\ensuremath{\mu XFA}$ beamline and multilayer laboratory

Reflection Crossed mirror pair (Kirkpatrick-Baez system)

$$NA = \Phi_{crit} \left(1 - \frac{\sqrt{2-q}}{\sqrt{2+q}}\right)$$

- 2 mirrors just touch with $q_h = l_h/r'_h = l_v/r'_v = q_v = q_v$ $r'_h + 0.5 q r'_h = r'_v - 0.5 q r'_v$ we put $r'_v = m r'_h$: then q = 2 (m-1)/(m+1)
- <u>at ELETTRA m=5: q = 1.33</u> $\Delta_{h,f} = \Delta_{v,f} = 1.1 \Phi_{crit} = 2 \text{ NA}$
- more realistic 2 NA = Φ_{crit}



OPERATIONAL example: ESRF (bendable flat mirror): f=95 mm and I=90 mm 2 NA = 0.8 Φ_{crit} R = $\lambda/(0.8 \text{ sqrt}(2\delta)) = R_{prac}$ = 5 * R_{single bounce capillary} exp: Φ =2.2 mrad at 20.5 keV

Werner Jark ELETTRA



ultimate limit practical limit experimental limit

µXFA beamline and multilayer laboratory





ultimate limit practical limit experimental limit

µXFA beamline and multilayer laboratory



Add multilayer coating becomes chromatic $R = 2 d \approx 6 nm$ **ESRF (bend mirror):** f=250 mm, l=170 mm 6.5 mrad, d = 8 nm R_{prac} ≈ 16 nm R_{exp} ≈ 86 μm figure error limited (Hignette, ESRF)

Werner Jark ELETTRA





ultimate limit practical limit experimental limit

µXFA beamline and multilayer laboratory



Werner Jark ELETTRA



ELETTRA

Spatial resolution

ultimate limit practical limit experimental limit

µXFA beamline and multilayer laboratory



For binary zoneplates (opaque in soft x-rays) r outermost period R = r/2R_{prac} ≈ 20 nm $R_{exp} \approx 20 \text{ nm} @ 2 \text{ nm}$ (CXRO, Berkeley) line width limit for lithographic processes





ultimate limit practical limit experimental limit

µXFA beamline and multilayer laboratory

Rings (thickness t) become transparent for x-rays. Need phase zoneplates:

rings retard by π t= $\lambda/(2\delta)$ and for circular ZP r_{min}=t/8 R_{prac}= r/2 = $\lambda/(32\delta)$ R_{exp} \approx 90 nm for r=206 nm t \approx 4.4 r @ λ =0.154 nm (Yun et al, RSI 1999) C. David et al, APL 2001 D r_{min} ≈ t/50 but r_{min} > 40 nm $R_{prac} = \lambda / (200\delta) > 20 \text{ nm}$

Werner Jark ELETTRA



ELETTRA

Spatial resolution

ultimate limit practical limit experimental limit

µXFA beamline and multilayer laboratory



better efficiency than binary zone-plates out-of-phase zoneplates could produce smaller focii above 10 keV with reduced efficiency



ultimate limit practical limit experimental limit

µXFA beamline and multilayer laboratory

<section-header>

www.accel.de

Chromatic lenses

Compound refractive lenses (concave) Snigirev et al, NATURE 1996



Lengeler @SRI2003 **x-rays:** $\underline{n = 1 - \delta - i\beta} < 1$

need of <u>concave</u> and parabolic lenses $f=Rad/\delta$ $I = 1/(\rho^*[\mu/\rho])$

lens transmission: T(y) = $exp(-y^2/2f\delta I)$

for d=0 Gaussian with $\sigma = sqrt(f\delta I)$

Werner Jark ELETTRA



ultimate limit practical limit experimental limit

µXFA beamline and multilayer laboratory





Diffraction limited spot size is obtained with spatially coherent incident radiation



e.g. S=30 μ m, A=1 mm, λ =0.154 nm: Q=200 m!!

Couldn't it be better to compress the beam?

School on Synchrotron Radiation and Applications In memory of J.C. Fuggle and L. Fonda, Trieste, 28/04/2004

Werner Jark ELETTRA



ultimate limit practical limit experimental limit

µXFA beamline and multilayer laboratory



Snell's law: $\phi_{ext} = sqrt(\phi_{int}^2 + \phi_{crit}^2)$

for $\delta_2 \ll \delta_3$: $D_{min} = \lambda/(2 \text{ sqrt}(2\delta_3))$ $R_{ult} = \lambda/(4 \text{ sqrt}(2\delta)) = R_{prac}$

same for capillaries and tapered waveguides (Bergemann, PRL 2003)

equation is identical to single bounce capillary

Werner Jark ELETTRA



ultimate limit practical limit experimental limit

μXFA beamline and multilayer laboratory



Waveguides rather inefficient with D=10 nm. However, D=70 nm and thus R=35 nm can be provided "easily" with high efficiency (Jark et al, APL 2001)

2-dimensional version was successfully produced (Pfeiffer et al, Science 2002) R: 35 nm x 65 nm

Werner Jark ELETTRA



ultimate limit practical limit experimental limit

µXFA beamline and multilayer laboratory

In scanning configuratio	ns, may be better in imaging
• ellipsoids, toroids	R > 5000 nm
 mono-capillaries 	R ≈ 5000 nm
• Kirkpatrick-Baez mirror pair (elliptical)	R = 83 nm
Fresnel zone-plates	R = 20 … 50 nm
• compound refractive	
lenses CRL	R ≈ 200 nm
• x-ray waveguides	R ≈ 35 nm
Verner Jark	School on Synchrotron Radiation and Application

ELETTRA



What is the spot size?

µXFA beamline and multilayer laboratory





X-ray Zoom lens: Do-It-Yourself!

µXFA beamline and multilayer laboratory



B. Cederström, R. N. Cahn, M. Danielsson, M. Lundqvist, D. R. Nygren: Focusing x-rays with old LP's Nature 404, 951 (2000)



Werner Jark ELETTRA



Get it almost for free

µXFA beamline and multilayer laboratory



Sawtooth comb milled into PLEXIGLASS in ELETTRA workshop [Marco De Gregorio, Gilio Sandrin]

For geometrical optics it is a lens with parabolic transmission function, i.e. an approximation of CRL

Werner Jark ELETTRA



Test it at home

µXFA beamline and multilayer laboratory



ELETTRA

In memory of J.C. Fuggle and L. Fonda, Trieste, 28/04/2004





µXFA beamline and multilayer laboratory



ELETTRA

In memory of J.C. Fuggle and L. Fonda, Trieste, 28/04/2004



A tiny plastic x-ray lens

μXFA beamline and multilayer laboratory



ELETTRA



A tiny plastic x-ray lens!

μXFA beamline and multilayer laboratory



Werner Jark ELETTRA



A tiny plastic x-ray lens!

µXFA beamline and multilayer laboratory



SIGMEDT OF OUT OFFICAL SOUTHTY OF AMERICA

VOLUME IS SUMBER 9. SEPTEMBER, 1945 1948

Formation of Optical Images by X-Rays

PAUL KIRKPATRICK AND A. V. BAEZ Stanford University, Stanford, California (Received March 12, 1948)

Several conceivable methods for the formation of optical point of central rays by a distance given approximately images by x-rays are considered, and a method employing by $S=1.5Mr^2/R$, where M is the magnification of the concave mirrors is adopted as the most promising. A con- image and r is the radius of the mirror face. The theoreticave spherical mirror receiving radiation at grazing inci- cally possible resolving power is such as to resolve point dence (a necessary arrangement with x-rays) images a objects separated by about 70A, a limit which is indepoint into a line in accordance with a focal length f = Ri/2 pendent of the wave-length used. Point images of points where R is the radius of curvature and i the grazing angle. and therefore extended images of extended objects may The image is subject to an aberration such that a ray be produced by causing the radiation to reflect from two reflected at the periphery of the mirror misses the focal concave mirrors in series. Sample results are presented.

INTRODUCTION

THE literature of x-rays contains many pasof focusing x-rays with lenses or mirrors. Both the thirty years later his successors understood why. fields of investigation closed to the optical micro-general practice has a value of the order of 10-5. the electron microscope because of the limited a single refracting surface of radius R is approxipenetrating power of electrons, X-ray spectrome- mately R/δ . For several surfaces in series, arlines had their designers possessed the means of large 8 and slight absorption. Unfortunately maoptical control available to workers with light in other spectral regions.

X-RAY LENSES Roentgen's1 first experiments convinced him ages deploring the supposed impossibility that x-rays could not be concentrated by lenses; difficulty and the regret are easily appreciated. A X-ray refractive indices are less than unity by an satisfactory x-ray microscopy would open up amount & which for common solids and x-rays of scope because of its restricted resolution, and to It may readily be shown that the focal length f of ters and diffraction instruments would probably ranged cooperatively, we have 1 $f = \delta(1/R_1 + 1/R_2)$ have evolved along simpler or more advantageous +etc.). To make a successful lens we require a



Collection of historical documents

Schwarzschild objective

suggested for use with multilayer coatings in the soft x-ray range at DESY, Hamburg, Germany:

P.-P. Haelbich, W. Staehr and C. Kunz Ann. N. Y. Acad. Sci., New York, 342, 148 (1980)

classical application: long distance objective for full field microscopy

here it is used in the reversed (demagnifying) orientation



Fig. 11. Cross section of a Schwarzschild objective with two spherical mirrors (from Haelbich et al. (1980)). Example for the actual parameters for a 10× objective with an aperture angle $\sin \frac{1}{2}\theta_a = 0.125$: diameter and radius of curvature for the big mirror, 4.4 and 13.409 cm, for the small mirror, 1 and 5.205 cm, mirror spacing 8.387 cm. (Example by R. Tibbetts, IBM.)

spot diameter < 0.1 jum adrieved very little tuning supabilities performance limited by scattering producing significant tails

38 Claims, 8 Druwing Shoets

	A	U3005654852A			
United States Patent (19)		[11] Patent Number: 5,684,852			
Tor	nie	[45] Date of Patent: Nov. 4, 1997			
[34]	X-RAY LENS	(58) Field of Search			
[75]	Investor: Taubibian Tamin, Troducts, Japan	359/709, 730, 744, 712, 713-717, 811; 378/345, 84, 140; 250/505.1			
[73]	Assignce: Approved Industrial Science & Technology, Ministry of Interestional Trade & Industry, Tokyo, Japan	[50] References Cited			
		U.S. PATENT DOCUMENTS			
1211	And No - 736 630	3,724,824 4/1973 Lonfant et al			
[22]	Filed: Oct. 25, 1996	Primary Examiner-Doc Wong Astorney: Agent, or Firm-Oblon. Spivak. McClelinod, Main: & Neortest, P.C.			
	Related U.S. Application Data	[57] ABSTRACT			
[62]	Division of Ser. No. 329,503, Peb. 16, 1905, Pat. 1 5,594,773.	No. An X-ray lene includes a plurality of hollow cylinders of			
1301	Foreign Application Priority Data	prescribed tadius bored in a leas material pieces having a phase lag coefficient appropriate for the wavelength of the			
Peb	18,1994 [JP] Japas	X-rays to be focused such that the axes of the bollow			
[51]	Int. CL4 G21K 1/	66 array anis.			

[51] Int. CL⁴ [52] U.S. CL G31K 1/66 . 378/345; 378/84; 2:50/505.1; 339/665; 359/811









A compound refractive lens for focusing high-energy X-rays

A. Snigirev*, V. Kohn†, I. Snigireva* & B. Lengeler*‡

* European Synchrotron Radiation Facility, BP220, F-38043 Grenoble

Cedex, France † Kurchatov, I. V., Institute of Atomic Energy, 123182 Moscow, Russia

THE development of techniques for focusing X-rays has occupied physicists for more than a century. Refractive lenses, which are used extensively in visible-light optics, are generally considered inappropriate for focusing X-rays, because refraction effects are extremely small and absorption is strong. This has lead to the development of alternative approaches^{1,2} based on bent crystals and X-ray mirrors, Fresnel and Bragg-Fresnel zone plates, and capillary optics (Kumakhov lenses). Here we describe a simple procedure for fabricating refractive lenses that are effective for focusing of X-rays in the energy range 5-40 keV. The problems associated with absorption are minimized by fabricating the lenses from low-atomic-weight materials. Refraction of X-rays by one such lens is still extremely small, but a compound lens (consisting of tens or hundreds of individual lenses arranged in a linear array) can readily focus X-rays in one or two dimensions. We have fabricated a compound lens by drilling 30 closely spaced holes (each having a radius of 0.3 mm) in an aluminium block, and we demonstrate its effectiveness by focusing a 14-keV X-ray beam to a spot size of 8 µm.

The index of refraction for X-rays in matter can be written as $n = 1 - \delta + i\beta$, where β is the absorption index and δ is the

1 Present address: Physikalisches Institut, RWTH Aachen, 52056 Aachen, Germany

NATURE · VOL 384 · 7 NOVEMBER 1996



FIG. 1 Schematic diagram showing the principles of X-ray focusing by a compound refractive lens (CRL). As $(1 - \delta)$ is smaller than 1 (where δ is the decrement of the refractive index), a collecting lens for X-rays must have a concave shape, a, A simple concave lens fabricated as a cylindrical hole in the material, b, A CRL consisting of a number (N) of cylindrical holes placed close together in a row along the optical axis, focuses the X-rays at a distance that is N times shorter compared to a single lens. R is the radius of the holes, d is the spacing between the holes, λ is the X-ray wavelength, and F is the focal distance for a parallel input beam.

refractive index decrement. Refraction being very small (δ is typically between 10⁻⁵ and 10⁻⁷), all attempts to date to build refractive lenses for X-rays have been unsuccessful. Recently, the discussion about refractive lenses has been revived. Suehiro, Miyaji and Hayashi3 have proposed a refractive lens of highatomic-number (high-Z) material for focusing X-rays. Michette4

49

latest improvements

Fig. 3. Schematic view of the parabolically shaped single and compound refractive lenses: R, radius of curvature; A, aperture of the lens; p, length of the single lens or the distance between the centers of the two neighboring holes for a compound lens. (a) Single parabolic refractive lens, (b) compound refractive lens with parabolically shaped holes, (c) compound refractive lens with parabolically shaped half-holes.

Table 1 Calculated CRL Parameters for Boron and Aluminum"

Lens Material, Hole Radius, <i>R</i> Focal Distance, <i>F</i>			Effective			
	Energy, E (keV)	Number of Holes, N	Aperture, A (µm)	Resolution σ (μm)	Real Gain, g	Length, L (mm)
	5	13	251	1	190	13
В	10	55	211	0.6	186	55
$R = 500 \mu m$	20	222	177	0.4	168	224
F = 1 m	30	501	160	0.3	166	506
	40	892	149	0.2	176	901
AJ	10	45	116	1	6	45
$R = 500 \mu m$	20	184	163	0.4	36	186
F = 1 m	30	417	160	0.3	60	421
	40	743	149	0.2	80	750

°Calculations were made in the following conditions: source size, 50 μ m; source-lens distance, 50 m; lens focal distance, F = 1 m; spacing between holes, $d = 10 \ \mu m$. G is the ideal gain in the intensity at the focus for a point source. The real gain g takes into account the finite source size and the attenuation of the x rays owing to absorption in the material between the holes.

Nanometer Spatial Resolution Achieved in Hard X-ray Imaging and Laue Diffraction Experiments

Donald H. Bilderback,* Stephen A. Hoffman, Daniel J. Thiel

Tapered class capillaries have successfully condensed hard x-ray beams to ultrasmall dimensions providing unprecedented spatial resolution for the characterization of materials. A spatial resolution of 50 nanometers was obtained while imaging a lithographically prepared gold pattern with x-rays in the energy range of 5 to 8 kiloelectron volts. This is the highest resolution scanning x-ray image made to date with hard x-rays. With a beam 360 nanometers in diameter, Laue diffraction was observed from the smallest sample volume ever probed by x-ray diffraction, 5 × 10⁻³ cubic micrometers.



Fig. 1. Profile of the inner diameter (ID) of a capillary measured with an optical microse The entering ID is 22 µm and the exit ID is 3 µm. The calculated trajectories of two rays from a parallel x-ray beam are shown. Ray 1 undergoes 12 successive bounces with a net throughput of 57%, as calculated by a twodimensional ray-tracing program that includes the x-ray reflectance for each bounce. Ray 2 undergoes 11 reflections with a net throughput of 61%. The average reflectivity per bounce exceeds 95%, and the total deflection angles are 2.3 and 2.2 mrad, respectively.

SCIENCE . VOL. 263 . 14 JANUARY 1994

J. Synchrotron Rad. (1994). 1, 37-42

X-ray

is about 3 mrad or 0.2°

Figure 1

X-ray Applications with Glass-Capillary Optics

D. H. Bilderback,^{a,b} D. J. Thiel,^{a,c} R. Pahl^a and K. E. Brister^a

^aCornell High Energy Synchrotron Source (CHESS), ^bSchool of Applied and Engineering Physics, and ^cDepartment of Biochemistry, Cell and Molecular Biology, Cornell University, Ithaca, NY 14853, USA

(Received 23 May 1994; accepted 23 June 1994)

An X-ray beam can efficiently be transmitted through a capillary

concentrator if reflection from the smooth walls takes place at

angles less than the critical angle of reflection. For hard X-rays and

typical borosilicate glasses, the critical angle for 10 keV X-rays

Journal of Synchrotron Radiation

ISSN 0909-0495 © 1994



of radius 2 pixels.

0.5 μm

Figure 2

201

Schematic diagram of X-rays passing through a perfect polycapillary concentrator. A device has been used to condense 6 keV X-rays to a diameter of 68 µm while enhancing the intensity (flux/area) by a factor of 5 (Hoffman et al., 1994b). Before pulling, the concentrator consisted of 330 parallel tubes of 18 µm inner diameter and 2 µm wall thickness (Gibson, 1994).



letters to nature

21. Bakhabi, A.K. Investigation of electronic conduction in protein and DNA: Prog. Biophys. Med. Biol. 48.147.753/14041 22. Ladik, I. Energy hands in DNA. Int. J. Quantum Chem. 4, 397-317 (1971).

Acknowledgements

We thank L. Gurevich for assistance in the fabrication and measurements; E. W. J. M. van der Drift, A. van der Enden, L. E. M. de Groot, S. G. Lemay, A. K. Lanaers-Sourling, R.N. Schouten, Z. Yao, T. Zilbtra, M. R. Zuiddan, M. P. de Haas, J. M. Warman, A. Storn, N. Kemding and J. Jortner for assistance and discussions; and E. Kramer and E. Yiklirim for the DNA characterization measurements. This work was supported by the Dutch Boundation for Eurohumontal Research on Matter (FCM).

Correspondence and requests for materials should be addressed to C.D. (e-mail: dekker@qt.tn.tudelft.nl.).

Non-destructive determination of local strain with 100-nanometre spatial resolution

S. Di Fonzo*, W. Jark*, S. Lagomarsino†, C. Glannini‡, L. De Caro‡, A. Cedola†§ & M. Müller§

* SINCROTRONE TRIESTE, SS 14 km 163.5 in Anna Science Park. 1. MOI 2 Resoversa - Trieste, Italy

* Istituto Elettronica Stato Solido (IESS) - CNR, V. Cineto Romano 42, 1-00156 Roma, Italy

[‡] Centro Nazionale Ricerca e Sviluppo Materiali (PASTIS-CNRSM), Strada Statale 7 Appia km 712, 1-72100 Brindisi, Italy

§ ESRF, BP 220, F-38043 Grenoble Cedex, France

Structure sizes of ~180 nm are now standard in microelectronics. and state-of-the-art fabrication techniques can reduce these to just a few tens of nanometres (ref. 1). But at these length scales, the strain induced at interfaces can locally distort the crystal lattice, which may in turn affect device performance in an unpredictable way. A means of non-destructively characterizing such strain fields with high spatial resolution and sensitivity is therefore highly desirable. One approach is to use Raman spectroscopy², but this is limited by the intrinsic -0.5-µm resolution limit of visible light probes. Techniques based on electron-beam diffraction can

achieve the desired nanometre-scale resolution. But either they require complex sample preparation procedures' (which may alter the original strain field) or they are sensitive to distortional (but not dilational) strain within only the top few tens of nanometres of the sample surface⁴³. X-rays, on the other hand, have a much greater penetration depth, but have not hitherto achieved strain analysis with sub-micrometre resolution⁶. Here we describe a magnifying diffraction imaging procedure for X-rays which achieves a spatial resolution of 100 nm in one dimension and a sensitivity of 10⁻⁴ for relative lattice variations. We demonstrate the suitability of this procedure for strain analysis by measuring the strain depth profiles beneath oxidized lines on silicon crystals. The crucial element of our set-up is a waveguide2.8 (WG in Fig. 1), which constitutes an unusual optical element for medium- and high-energy X-rays (10-30 keV). Unlike diffracting optical elements it does not focus a collimated incident beam, but instead confines it (through a resonance effect*) in one direction to a dimension of typically 100-150 nm, the distance between the parallel interfaces of the resonator*. Several resonator modes can be excited; these modes can leave at the end of the waveguide, with a high degree of spatial coherence in the plane perpendicular to the waveguide surface, which is here the vertical one. In this direction, the beam profile of the first resonance mode-at distances of more than 1 mm from the waveguide end-is well described by a gaussian beam^{10,11}; this mode then seems to originate from a virtual line source inside the resonator. This has allowed us to register an in-line hologram with a spatial resolution of 140 nm in one direction¹². The idea behind the present diffraction imaging experiment is as follows: for highly monochromatic X-rays, a perfect crystal has a limited angular acceptance (typically a few tens of microradians) in its diffraction plane, which in our geometry in Fig. 1 is the horizontal plane. But in the vertical plane, its angular acceptance is larger and can even exceed 1 mrad. This acceptance can be matched favourably with the characteristics of the waveguided beam, which is divergent (typically 1 mrad) in the vertical plane while maintaining its collimation in the horizontal plane. Strain sensitivity is then achieved with the collimated beam in the horizontal plane. High spatial resolution is utilized in the vertical direction, in which local structural variations at the sample are registered by projecting them, magnified, on a two-dimensional detector placed far from the sample. So spatial resolution and strain resolution are not correlated, as they are obtained in orthogonal directions: spatial resolution in the horizontal plane has to be sacrificed in order to obtain good strain sensitivity.



Figure 1 Diffraction imaging set-up. The beam amining on the waveguide (WG surface is detector positioned at a fixed scattering angle 2#). The waveguide disperses the beam in spatially compressed by the waveguide in the vertical direction; the beam leaving the waveguide is vertically divergent. This latter beam, impinging on the sample surface at an incident angle ω , is diffracted in the horizontal plane towards the two-dimensional CCD

the vertical plane providing at the CCD detector a magnification $M = (Z_1 + Z_2)/Z_1 - Z_2/Z_1$ for any structural variations occurring at the sample surface in this plane. Z is the WGsample distance, Z_i is the sample-detector distance. In a Bragg scan only ω is varied.

S. Di Fonzo et al, Nature 403, 638 (2000)



Figure 4 Spatial variation of strain under different oxidized stripes. The experimental data (symbols) indicate the position of the Si (004) Bradd peak in reciprocal space as a function of the lateral position on the sample. The data are presented as $\Delta S_2 = S_2 - S_2$, where S_{--} is defined in the text, and S refers either to the position of a fitted single peak or to the position of a detectable second peak. These peak positions are derived from fits of gaussian peaks (single or double) to the integrated I(S) curves. The values of ΔS , are presented for two zones of the sample corresponding to the wide SiO₂ stripe (a) and to two narrow sub-micrometre SiO₂ stripes (b). For comparison, the height profile of the sample as obtained by the scanning AFM measurements is shown as an inset at the top of each panel.

🛤 © 2000 Macmillan Magazines Ltd NATURE VOL 403 10 FEBRUARY 2000 www.nature.com



Figure 2 Atomic force microscopy scan of sample height profile. The SO_2 stripes of different width extend ~ 170 nm above the sample surface.